

# Tantalum Oxide Resistive Memory Devices by IAD

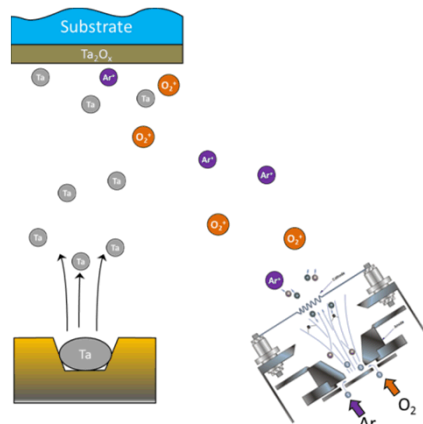
**EM-WeM-1, Wednesday 8:00AM**

**Ronald S. Goeke<sup>1</sup>, M.J. Marinella<sup>2</sup>, D.R. Hughart<sup>2</sup>, and S.A. Decker<sup>2</sup>**

*Materials Science and Engineering Center<sup>1</sup>*

*Microsystems Science and Technology Center<sup>2</sup>*

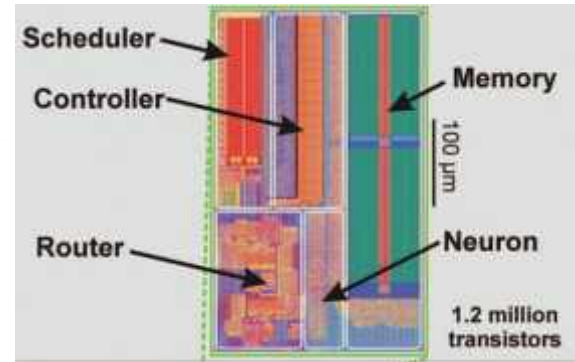
*Sandia National Laboratories, Albuquerque, NM, USA*



# Neural-inspired Computing Hardware

## Revival of an Old Idea

DARPA , IBM TrueNorth (2014):



Mark I Perceptron (Rosenblatt 1960):



Arvin Calspan Advanced Technology Center; Hecht-Nielsen, R. *Neurocomputing* (Reading, Mass.: Addison-Wesley, 1990); Cornell Library;

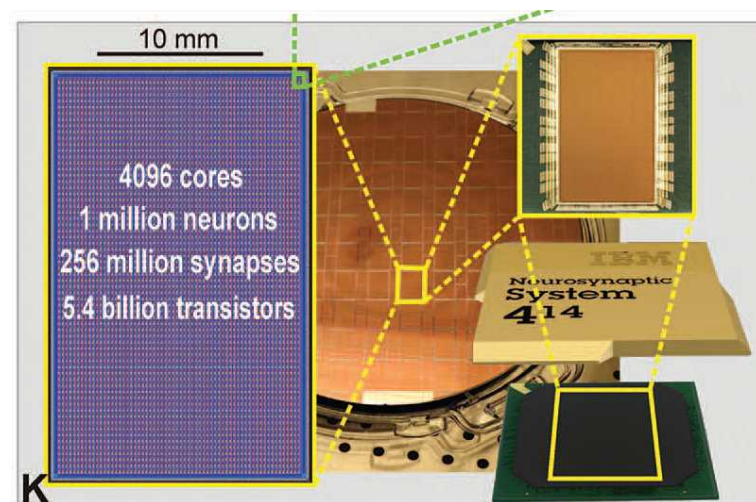
EU HBP, SpiNNaker (2014):



# Neural Algorithm Computing

## Current State of the Art

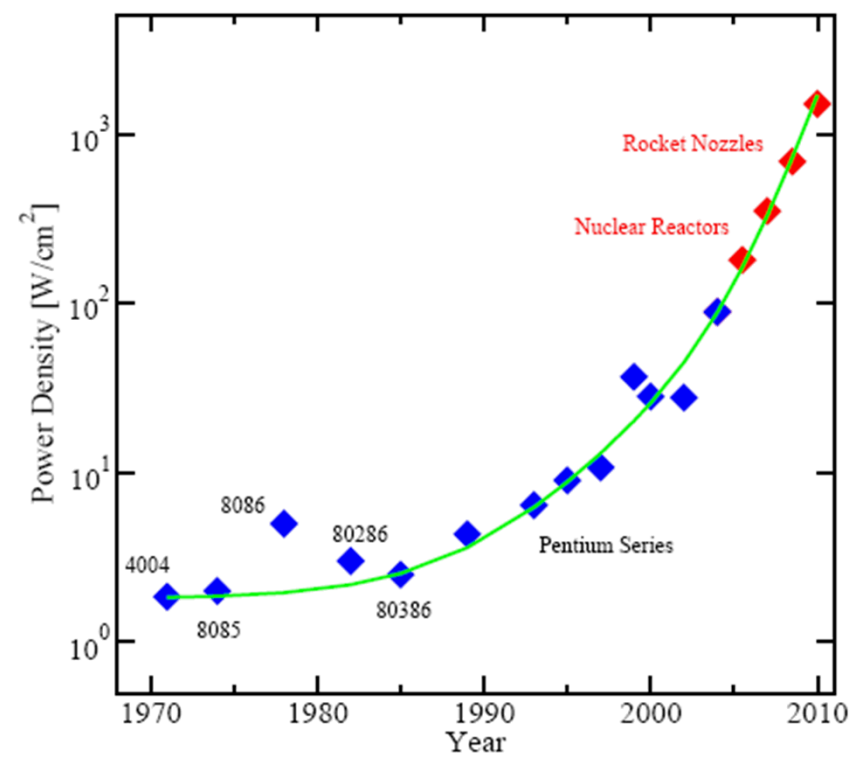
- **CPU/GPU**
  - Most general; common programming languages
  - Lowest power efficiency and performance
  - Memory separate from chip
  - Example: Google deep learning study (CPU→GPU)
- **FPGA**
  - General; requires hardware design language
  - Moderate performance and efficiency
- **Custom IC (Truenorth, Spinnaker)**
  - Specific: ex. executes STDP
  - Highest performance and efficiency
  - Expensive, 40MB local memory
  - Example: IBM Truenorth
- **Power ends up as a limiting factor**





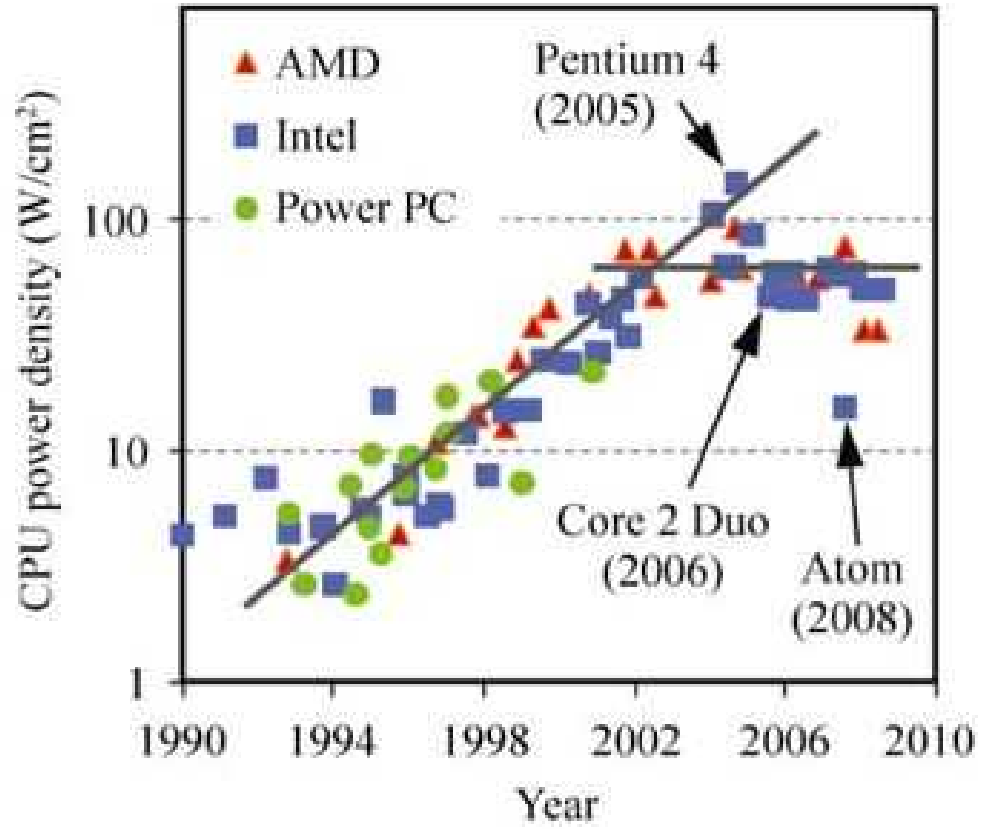
# Heating During Computing is Enormous

Low power RAM needed



(a) Power loss density per die

<http://www.iue.tuwien.ac.at/phd/holzer/node11.html>



<http://www.nanotechnologies.qc.ca/blog/industry/energy-dissipation-nanoscale-devices>



# Power Consumption is Also Enormous

## Possible solution?

New devices and new computing paradigms will be needed in the near future.



- Tianhe-2 - World's Fastest Supercomputer
- $\sim 3.4 \times 10^{16}$  flops/s,  **$\sim 20$  MW, room-sized**
- Nuclear reactors will soon be needed for every supercomputer.



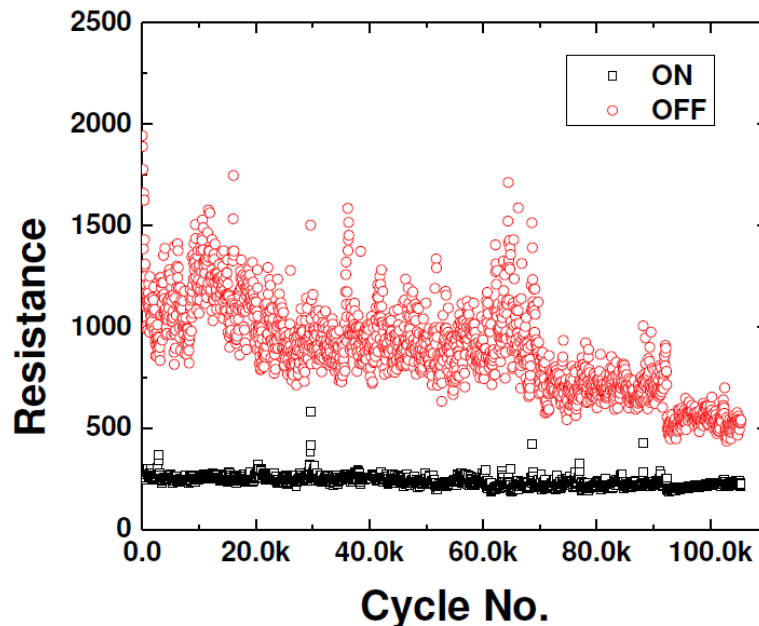
- The Human Brain
- **20W, 1200 cm<sup>3</sup>**
- $\sim 10^{18}$  flops/s are believed to be needed for the human brain project.

# Can Memristors Help?

## ReRAM

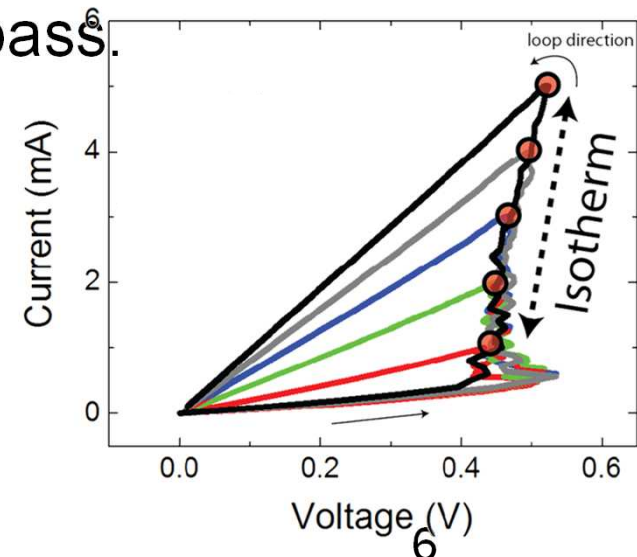
### Resistive Memory

- A voltage or current can change the resistance to a 1 or a 0.



### Novel Circuit Element

- Using partial voltages causes only partial changes.
- Similarly to synapses - as current passes, it becomes easier for more current to pass.



# Why Do We Need an HW Accelerator?

## Significant power savings

Problem: perceptron network training slow and extremely computationally intensive

Use simulation results for similar algorithm as example

Significant power savings using a memristor-based HW accelerator :

**16x reduction in power over SRAM ASIC**

**6x reduction in chip area over SRAM ASIC**

Equivalent to 6x improvement in performance/area

Example 1: 25,600 neurons 100,000 iterations/s					
Configuration	# of chips	Chip area (mm <sup>2</sup> )	% active	Power (W)	Power eff. over Xeon
Memristor Analog (config 4)	1	5.9	38.6%	0.07	234,859
Memristor Digital (config 5)	1	18.2	89.6%	0.62	16,968
SRAM (config 6)	1	29.1	89.6%	1.13	8,215
NVIDIA M2070	12	529.0	99.2%	2700.00	6
Intel Xeon X5650	179	240.0	99.9%	17005.00	1

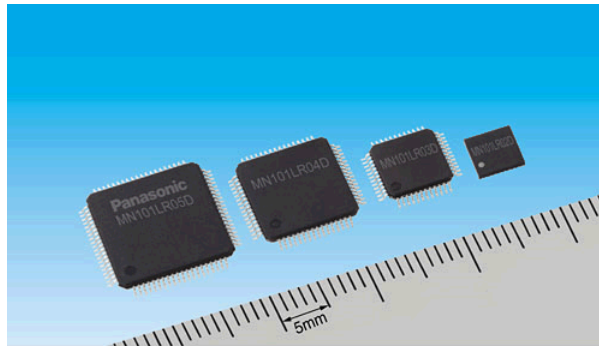
# Memristors

## Who's interested

### Resistive Memory

- Panasonic recently released the first product.

**Panasonic**  
ideas for life

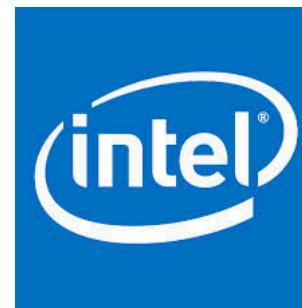


ReRAM Mounted Low Power Consumption Microcomputer, MN101LR Series

- They claim it is 5-10 times faster using half the power.
  - Probably saved in the wires.

### Novel Circuit Element

- Brain-inspired computing using memristors is receiving heavy investment from big companies.



Sandia  
National  
Laboratories



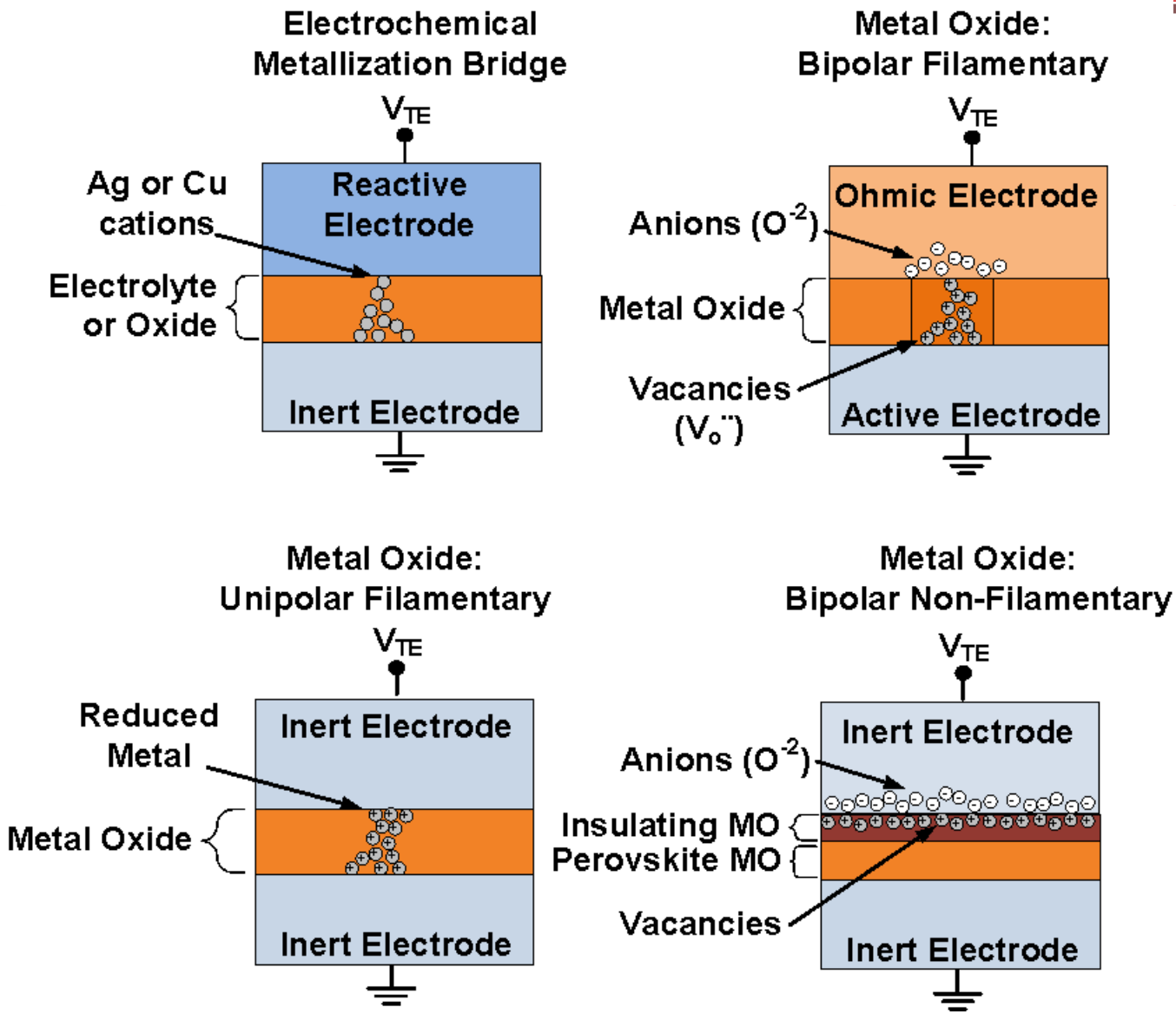
# Brain Inspired Computing at Sandia

## HAANA

- Sandia established a multidisciplinary LDRD project in neuromorphic computing project in October 2015
  - Hardware Acceleration of Adaptive Neural Algorithms (HAANA)
  - Algorithms research
  - Hardware and Device Architectures
  - Resistive Memory Devices
- Some of the initial work on development of resistive devices covered in this talk

# Resistive Random Access Memory

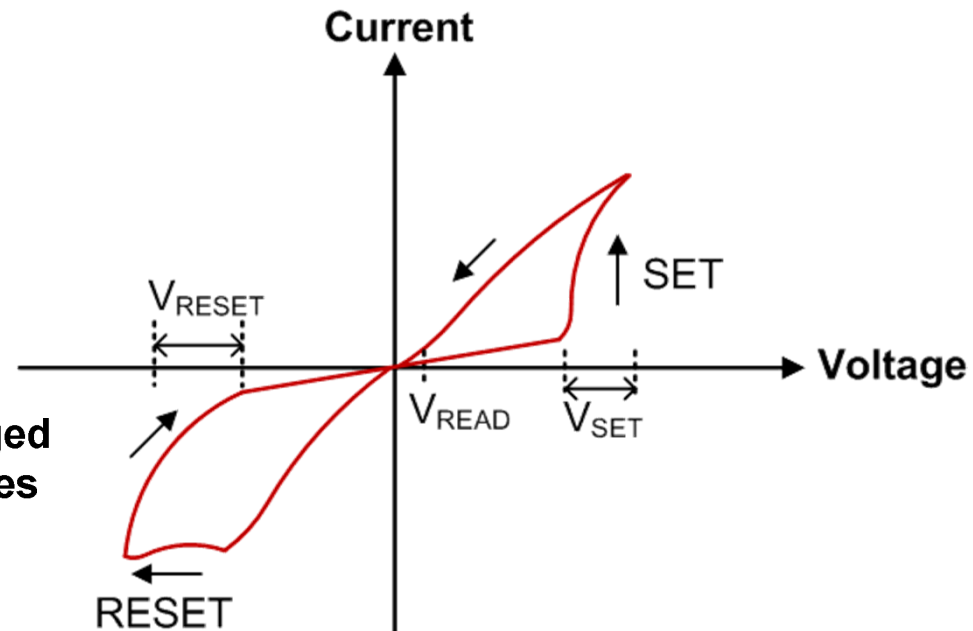
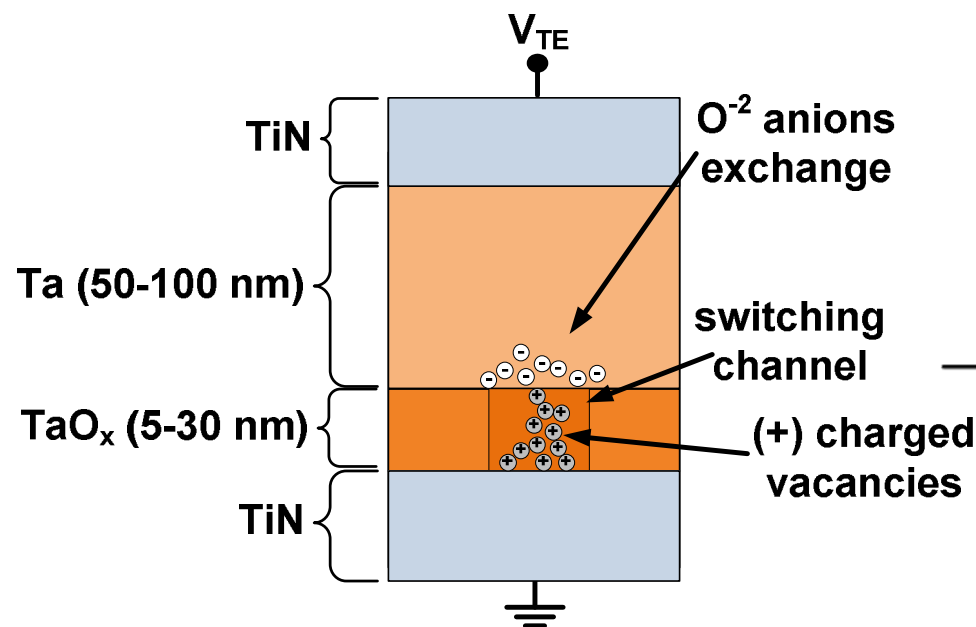
ReRAM



# Valence Change ReRAM

TaO<sub>x</sub>

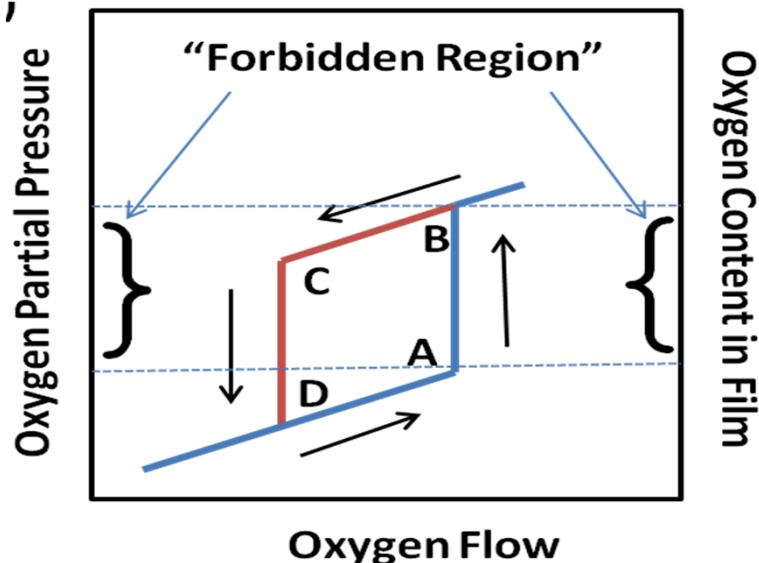
- “Hysteresis loop” is simple method to visualize operation
  - (real operation through positive and negative pulses)
- Resistance Change Effect (polarities depend on device):
  - Positive voltage/electric field: low R – O<sup>2-</sup> anions leave oxide
  - Negative voltage/electric field: high R – O<sup>2-</sup> anions return
- Common switching materials: TaO<sub>x</sub>, HfO<sub>x</sub>, TiO<sub>2</sub>, ZnO



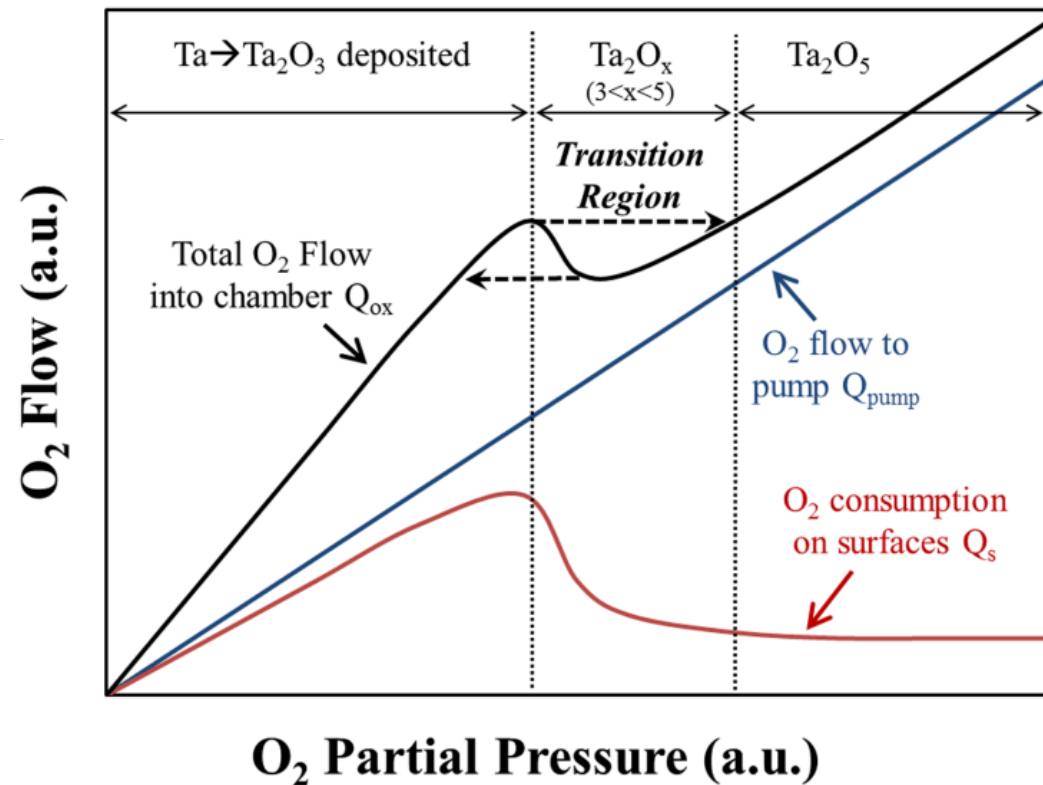
# Switching Film Development:

## Reactive Sputtering “Forbidden Region”

- One of the parameters that we vary is oxygen content
- Forbidden oxygen flow-pressure region occurs due to target poisoning
  - This is the region we need to be in to get ideal ReRAM stoichiometry



A.J. Lohn et al APL 103, 063502 (2013)



J.E. Stevens et al, J. Vac. Sci. Technol. A 32, 021501 (2014)

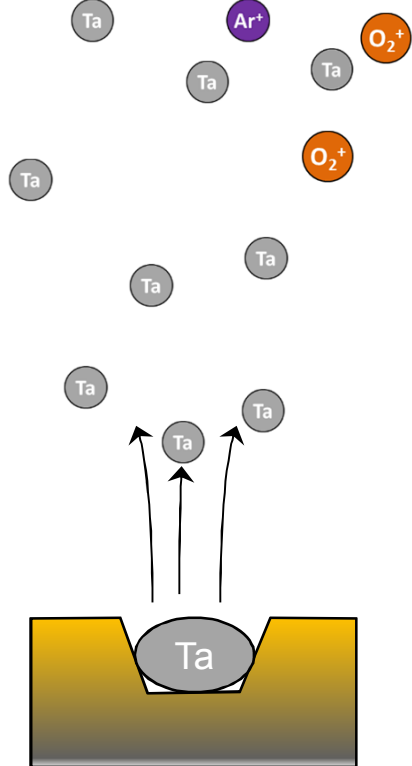
# Ion Assisted Deposition (IAD)

## Stoichiometry control

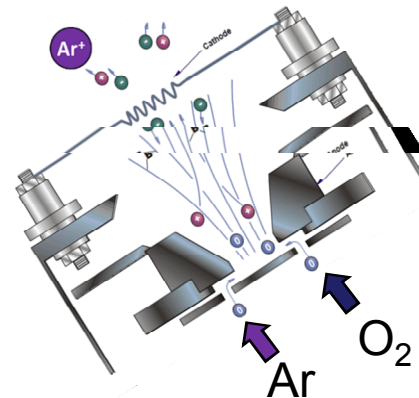
Metal Evaporation  
Rate Control

QCM

Substrate  
 $Ta_2O_x$



Oxidation control  
Ion Beam Current  
Gas flow rate  
%  $O_2$  in  $Ar/O_2$  gas mixture



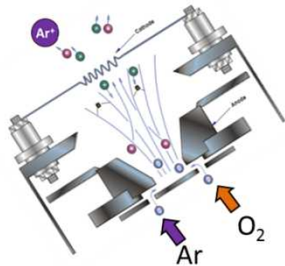
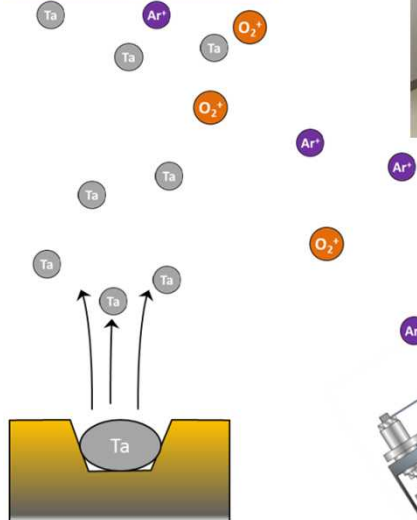
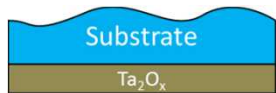


# Ion Assisted Deposition (IAD)

System used for  $\text{Ta}_2\text{O}_x$  deposition

0.5Å/s growth rate

33cm source to substrate



Ta source



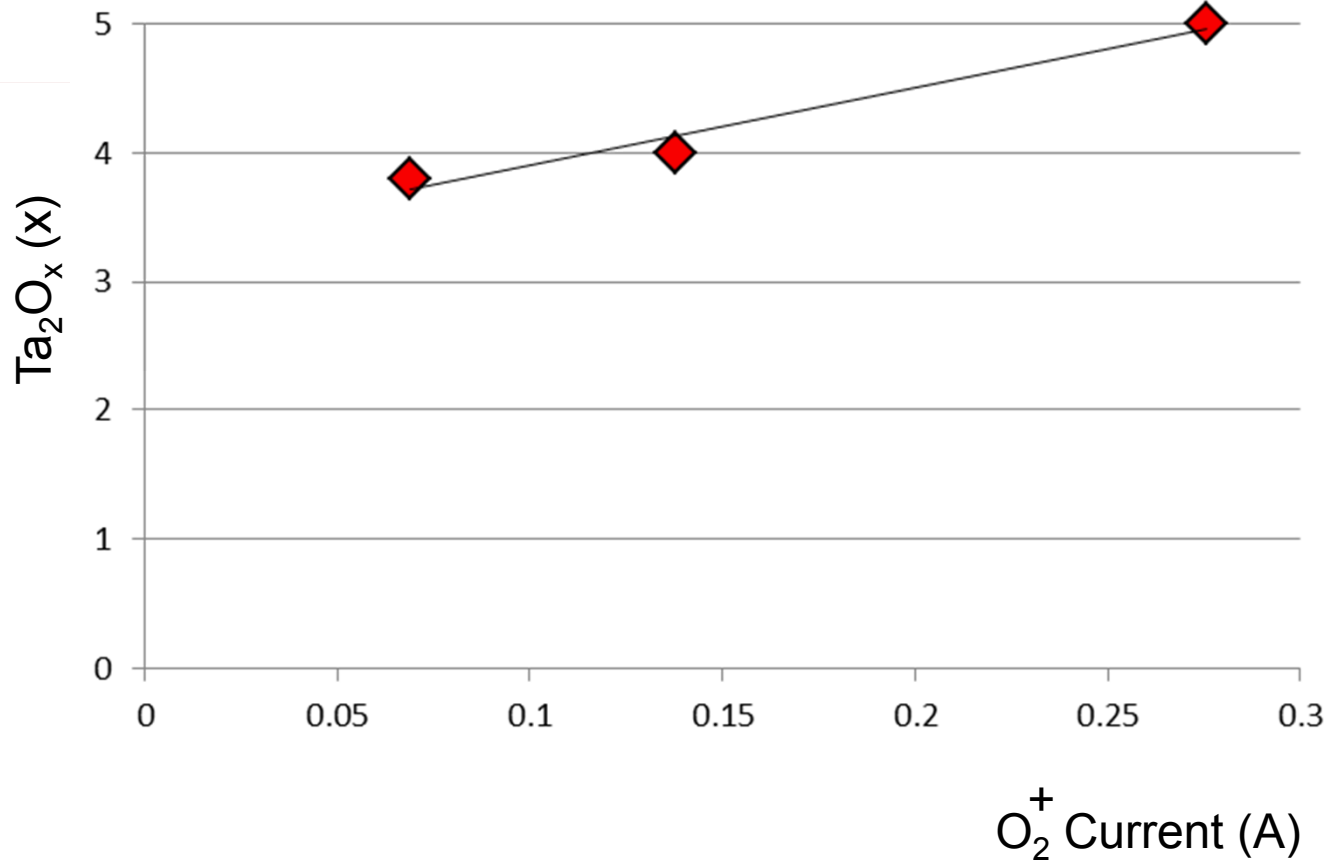
*Four pocket rotary turret  
10kV electron beam gun,  
and molten material during  
deposition*



KRI EH200 ion gun  
Gas mixture of Ar & O<sub>2</sub> @ 18 sccm

# Stoichiometry Control

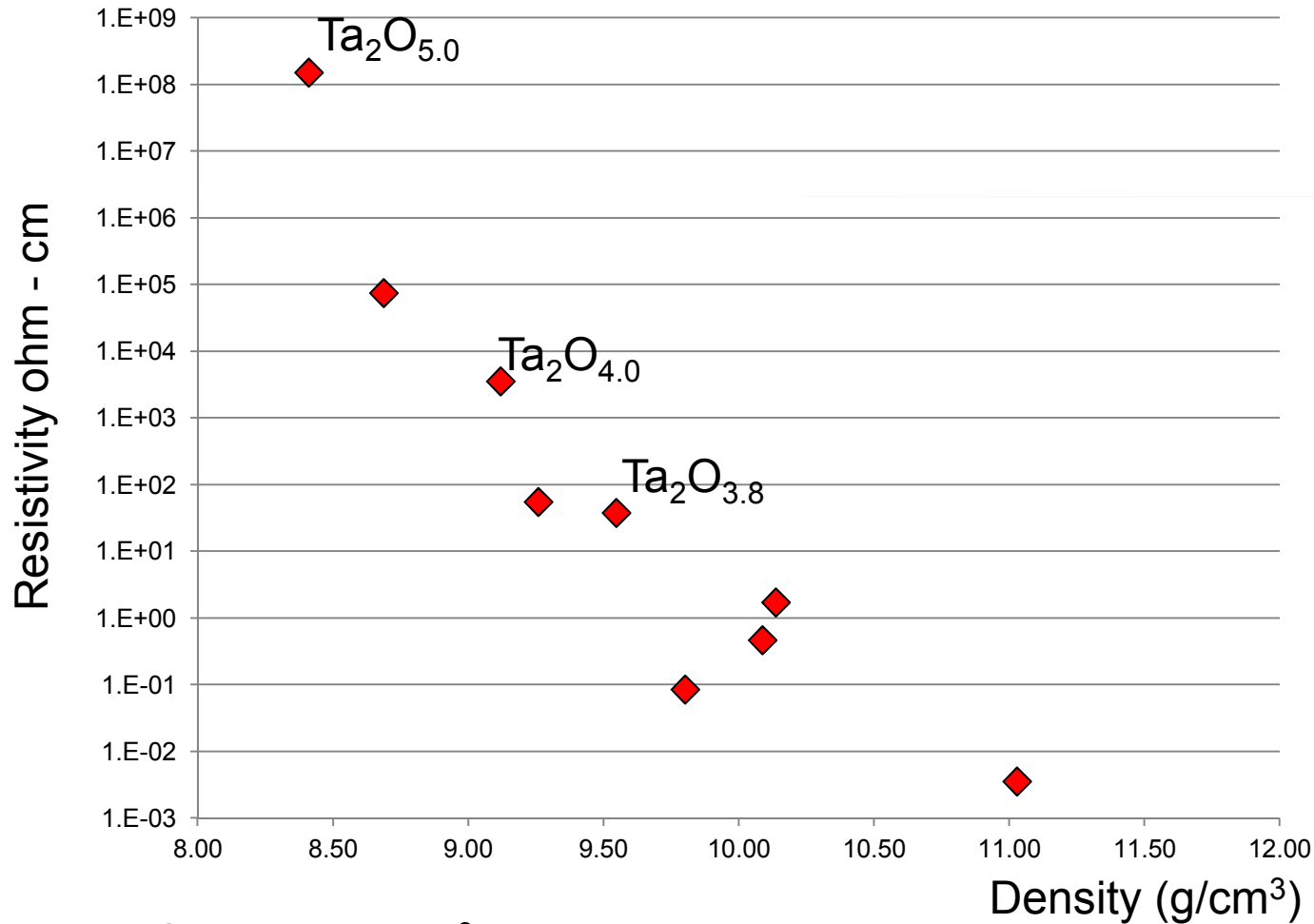
Ions and  $O_2$  partial pressure



Ions contribute to system pressure and also react with growing film

# IAD Film Resistivity

Density, resistivity and stoichiometry correlated

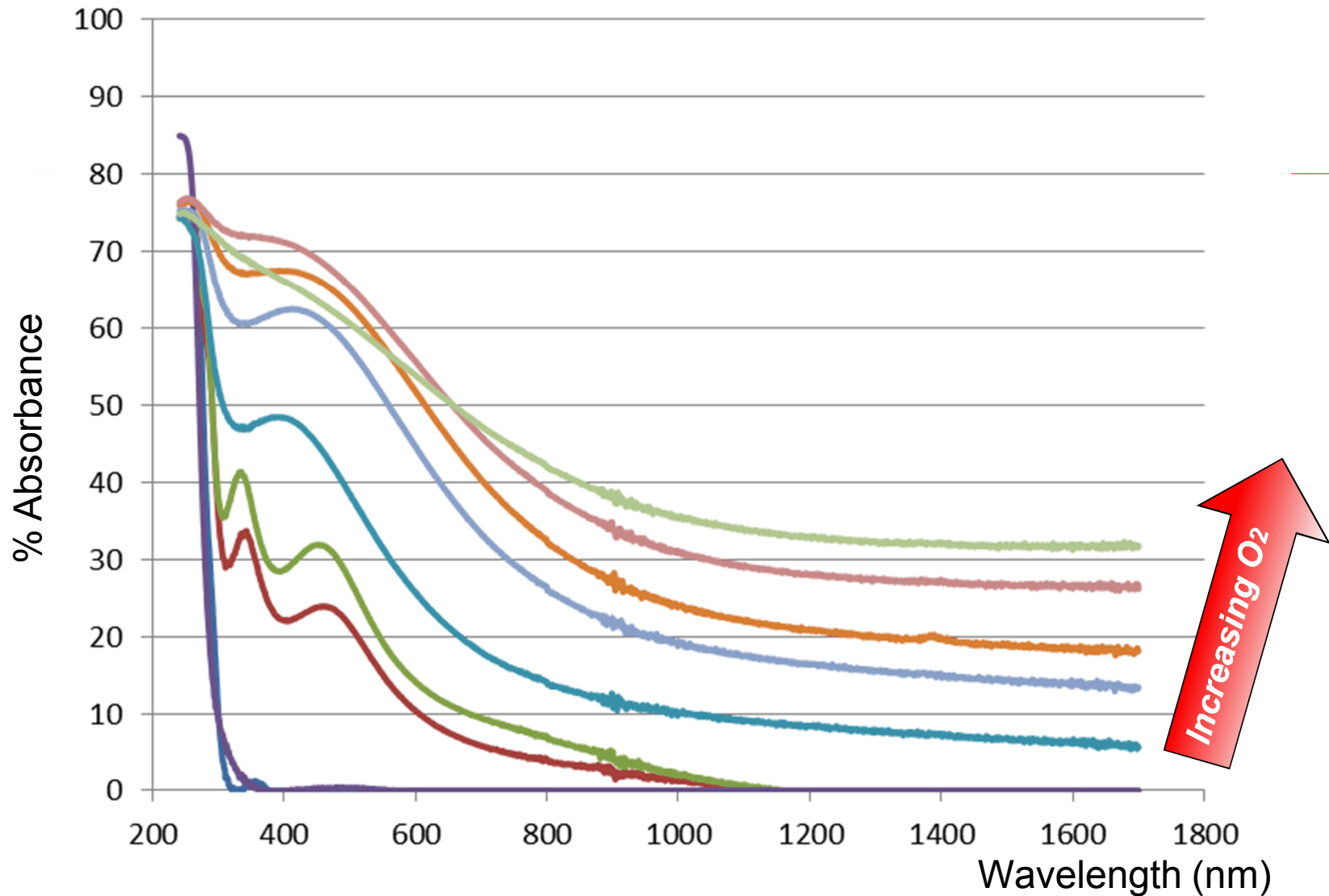


$\text{Ta}_2\text{O}_5 = 8.37 \text{ g/cm}^3$

$\text{Ta} = 16.69 \text{ g/cm}^3$

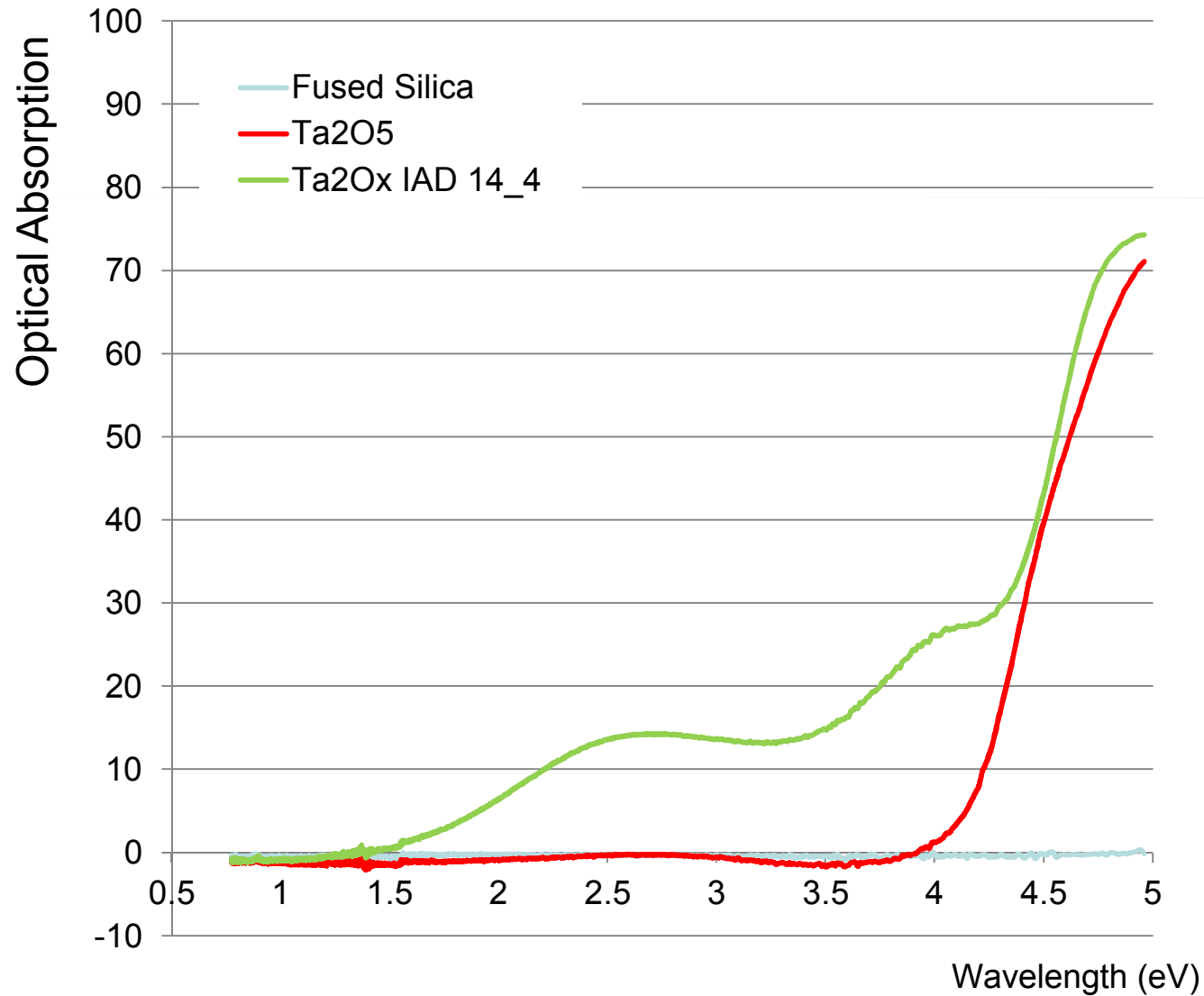
# Optical Absorption

## Spectrophotometry and Ellipsometry



# Band Gap Shift

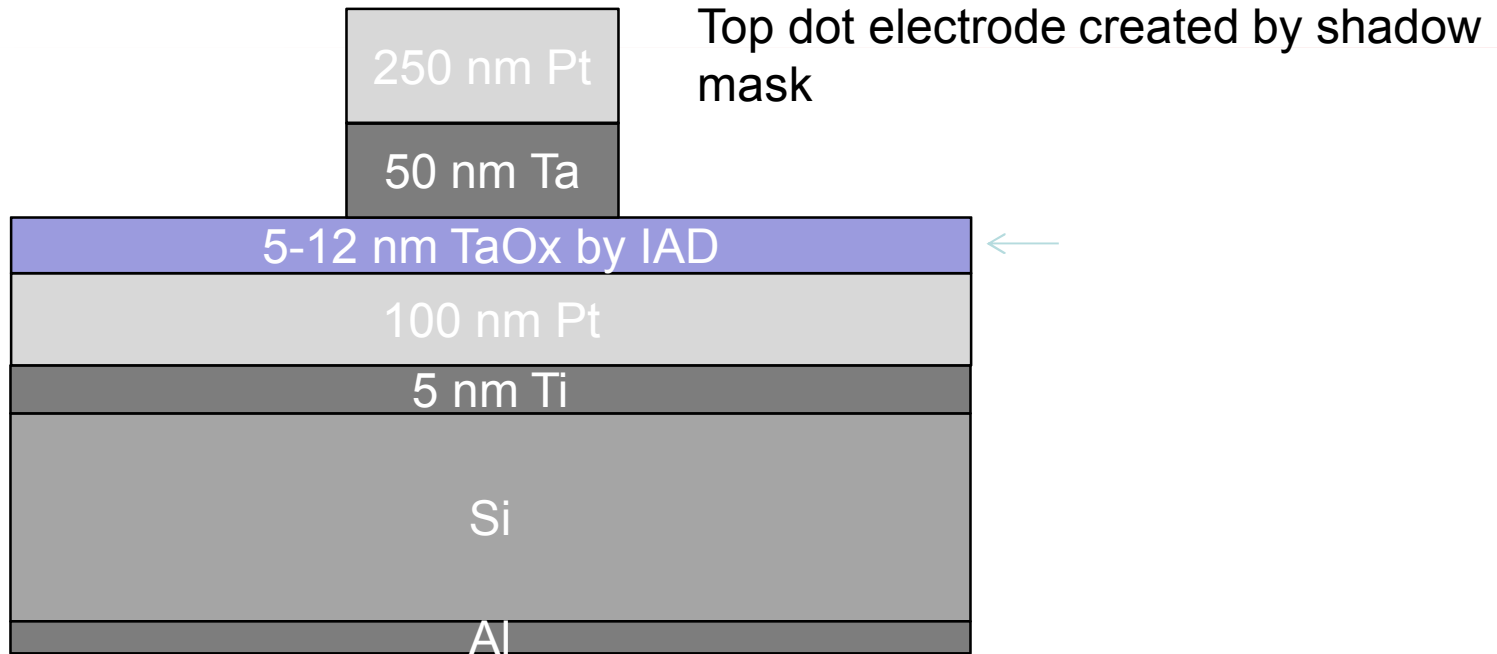
## Optical Absorbance





# Test Device

## Layer structure



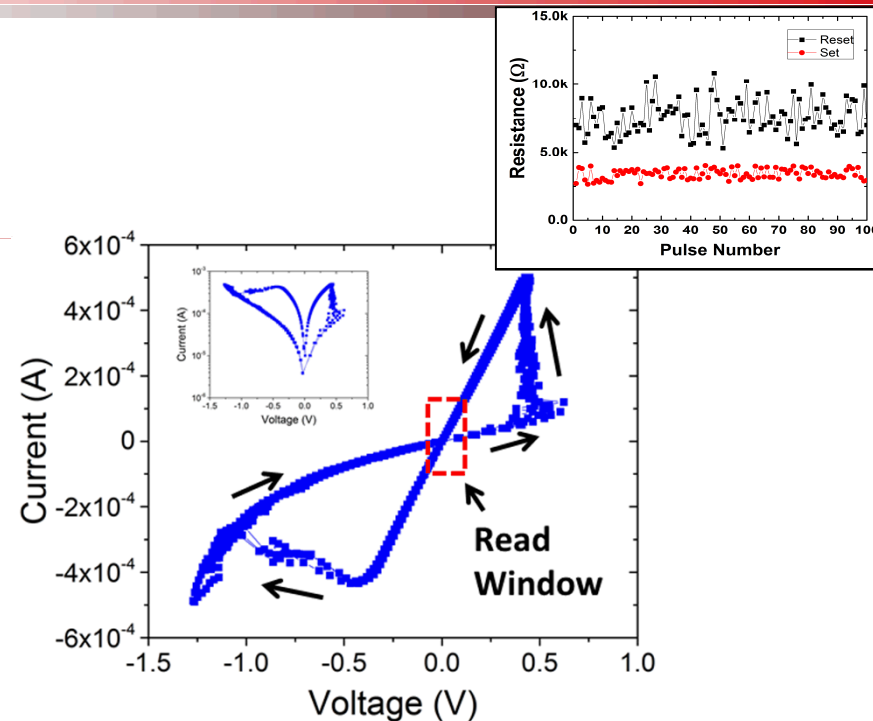
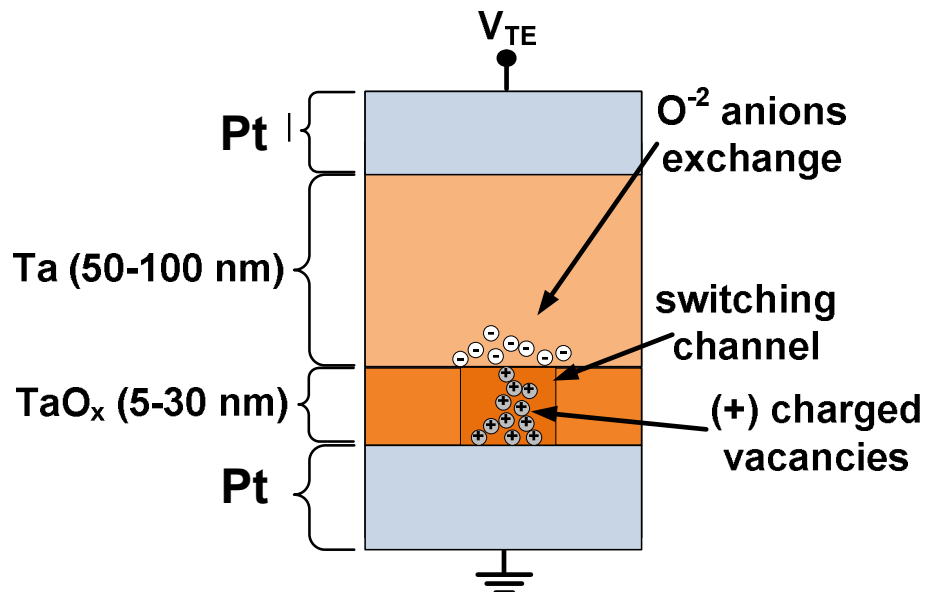
# Memristor I-V Characteristics

- Resistive RAM stores state in the form of resistance
- Applied current and voltage can change resistance state

– Hysteresis loop

- Low voltages can read state

– Read window

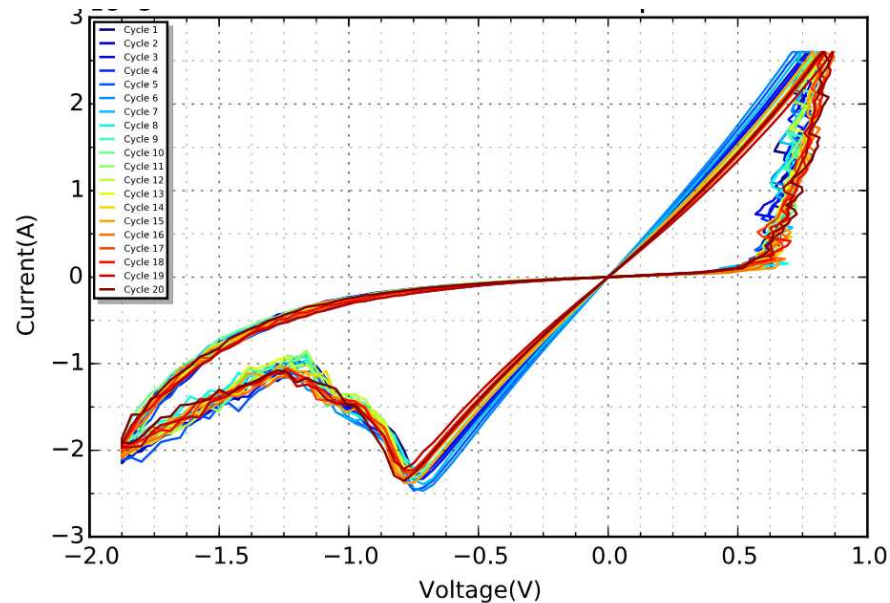


- Resistive switching
  - Oxygen vacancies
- TaO<sub>x</sub>
  - Oxygen anions

# IAD Improvements

## High Repeatability

- More precise control over film thickness, stoichiometry and reduction in surface roughness
  - Improvements in yield and uniformity
  - Process adjustments easier due to higher repeatability



# Ta<sub>2</sub>O<sub>x</sub> by IAD:

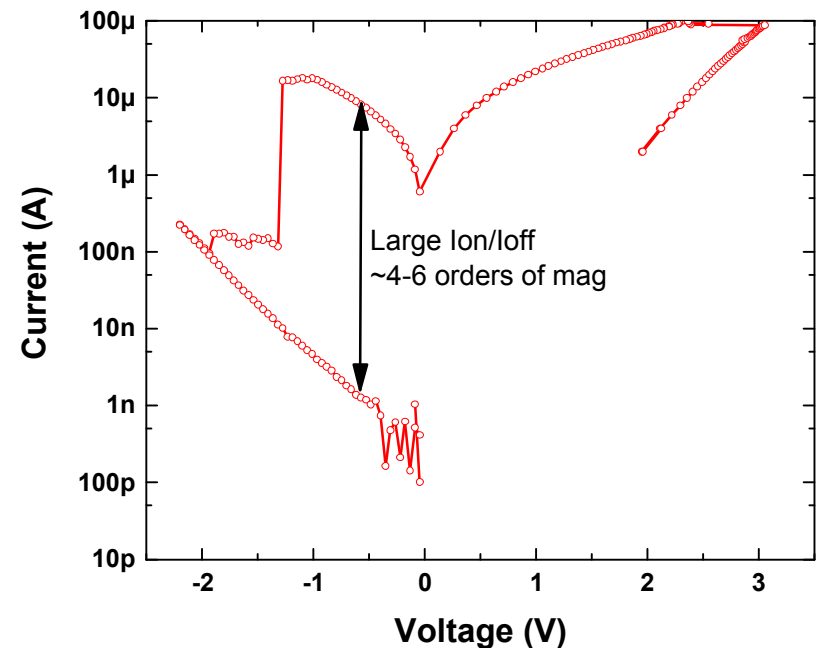
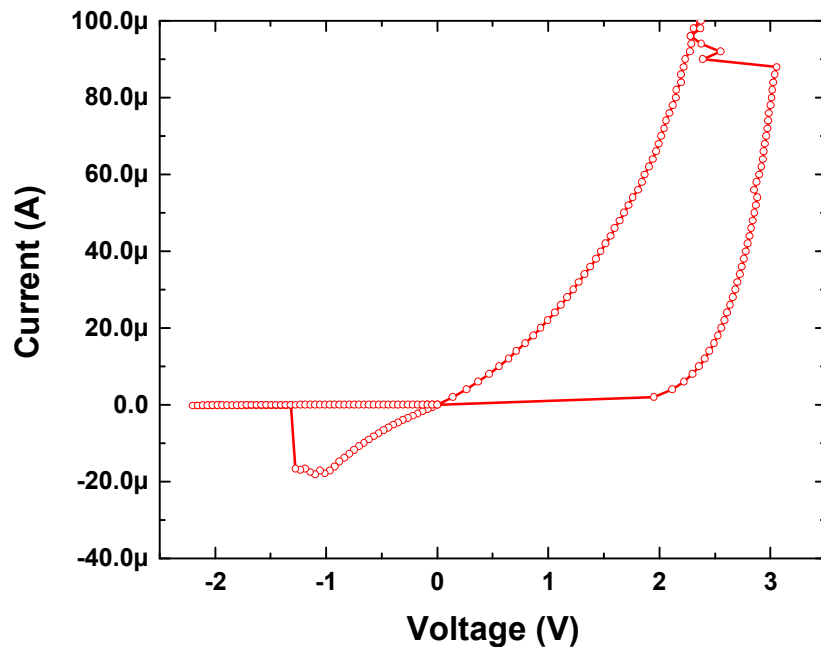
## Device Results

High yield; some batches 100% working devices

High resistance operation

Very high R<sub>off</sub>/R<sub>on</sub> ratio; as high as 6 orders of magnitude – critical for analog applications

Highly nonlinear IV curve – may provide self-selection



# Conclusions

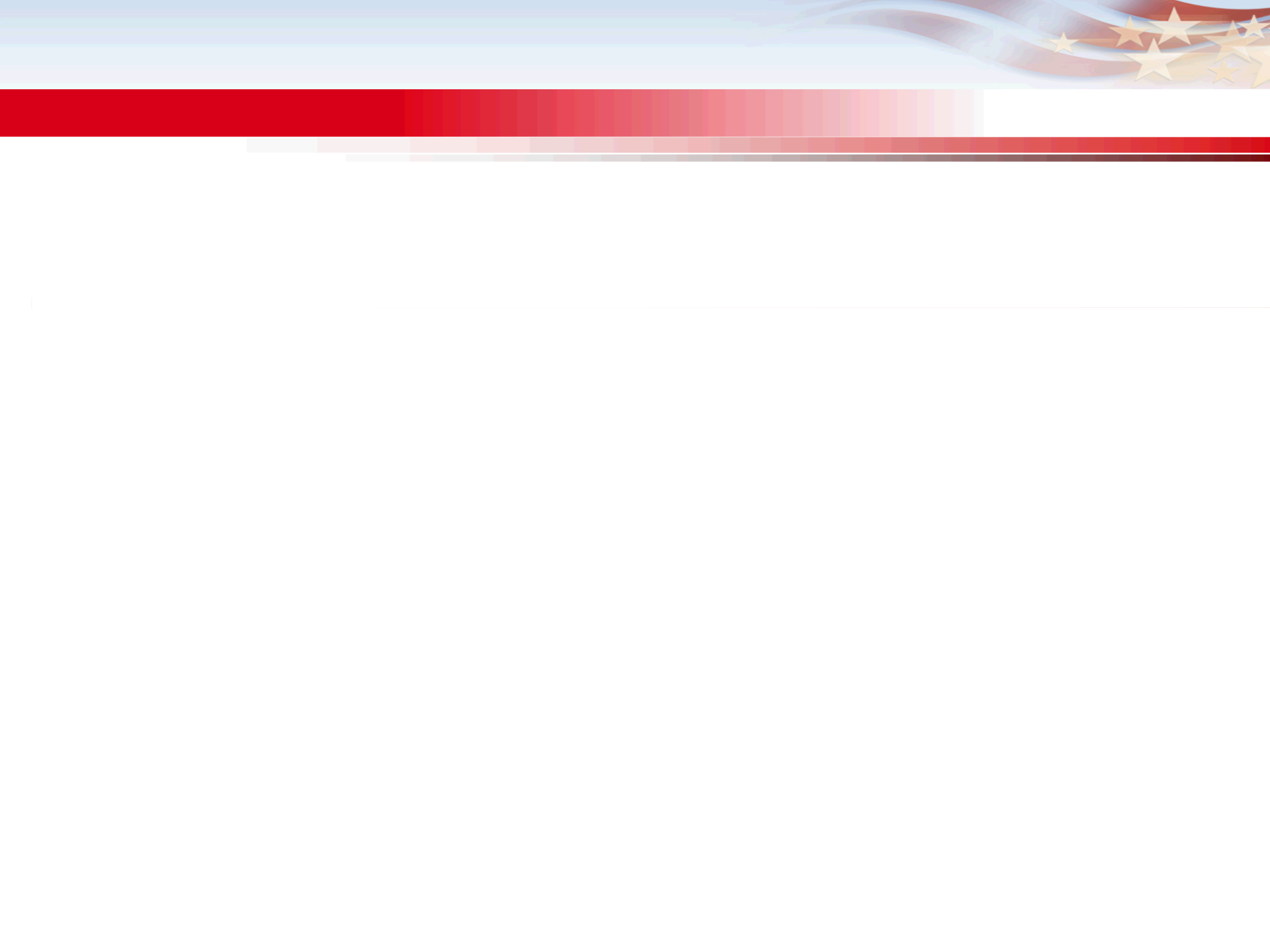
- Previous Metal Oxide ReRAM cells have relatively high cycle to cycle variability, which may significantly limit the resolution of an analog accelerator
- Ion Assisted Deposition of TaOx shows promise for significantly reducing that variability and improving device performance.
- IAD demonstrated excellent control over stoichiometry

## Acknowledgements:

This project is funded by Sandia's Laboratory Directed Research and Development (LDRD) Program.

Carl Smith for film deposition.





# Neural Algorithm Computing

## Next Generation

**Problem:** neural algorithm training requires significant memory and logic interaction

What is the most efficient way to combine memory, logic and interconnects?

SRAM: on chip cache memory is limited to ~40MB digital (Intel E7)

ns latency, max regardless of CPU, GPU or ASIC

Off chip communication to DRAM costs >100 pJ/op, ~10ns latency

Resistive memory on chip: can be stacked to >TB/cm<sup>2</sup>, >100 layers

On chip access, <pJ per op and <1ns latency possible

Terabit densities on single chip – on chip wiring is low energy!

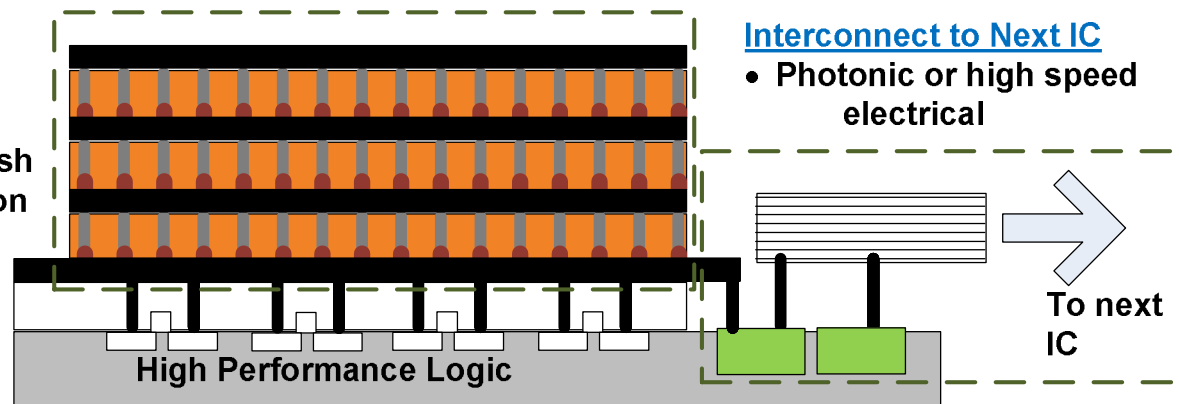
Sub 1V switching – minimal  $CV^2f$  loss (DRAM 2-5V)

Significant power savings using a ReRAM based HW accelerator

**Example: Taha found 16x reduction in power, 6x improvement in perf per chip over SRAM**

### ReRAM Layers:

- Terabit cm<sup>-2</sup> per layer
- Replaces DRAM & flash
- <1 pJ, <10 ns operation



# Data Centers are Expanding Rapidly

Problems for analysis and energy consumption

